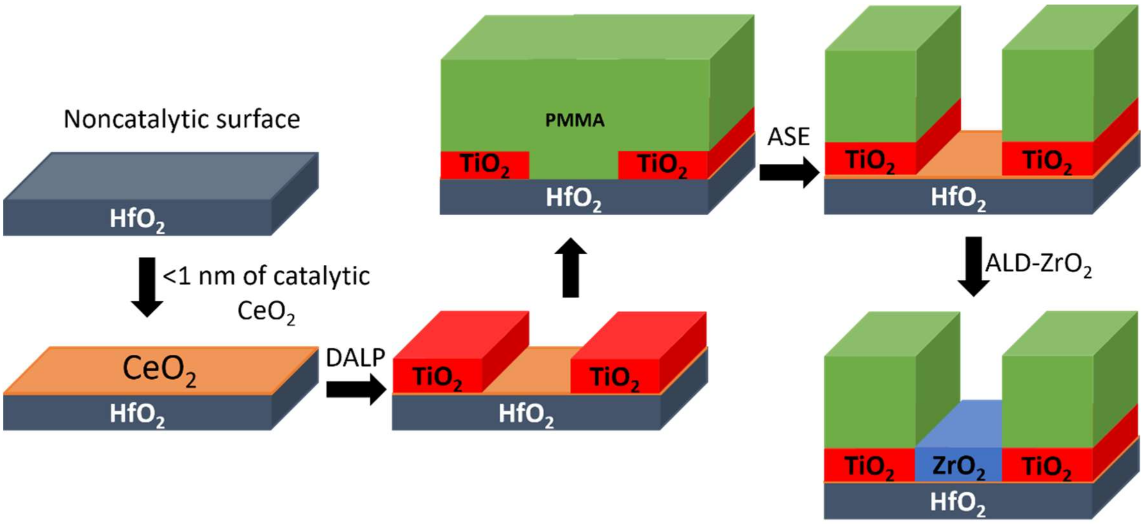

Figure 1 – Schematic depiction of the whole process.

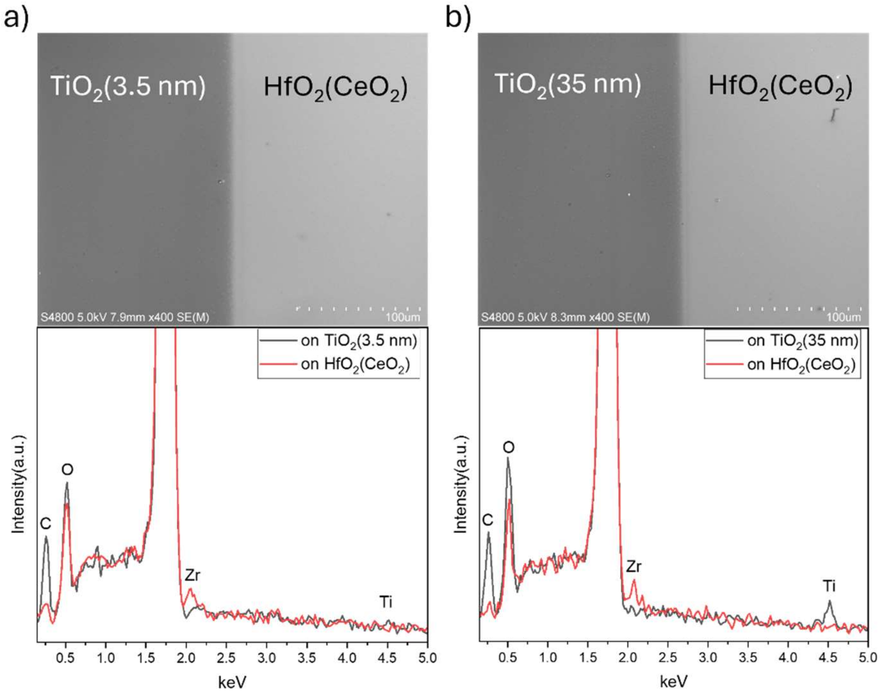

Figure 2 - SEM images and EDS spectra of the TiO_2/HfO_2(CeO_2) structure after ASE of PMMA at 275 °C for 60 min followed by AS-ALD of ZrO_2 with (a) 3.5 nm and (b) 35 nm thick TiO_2 lines.

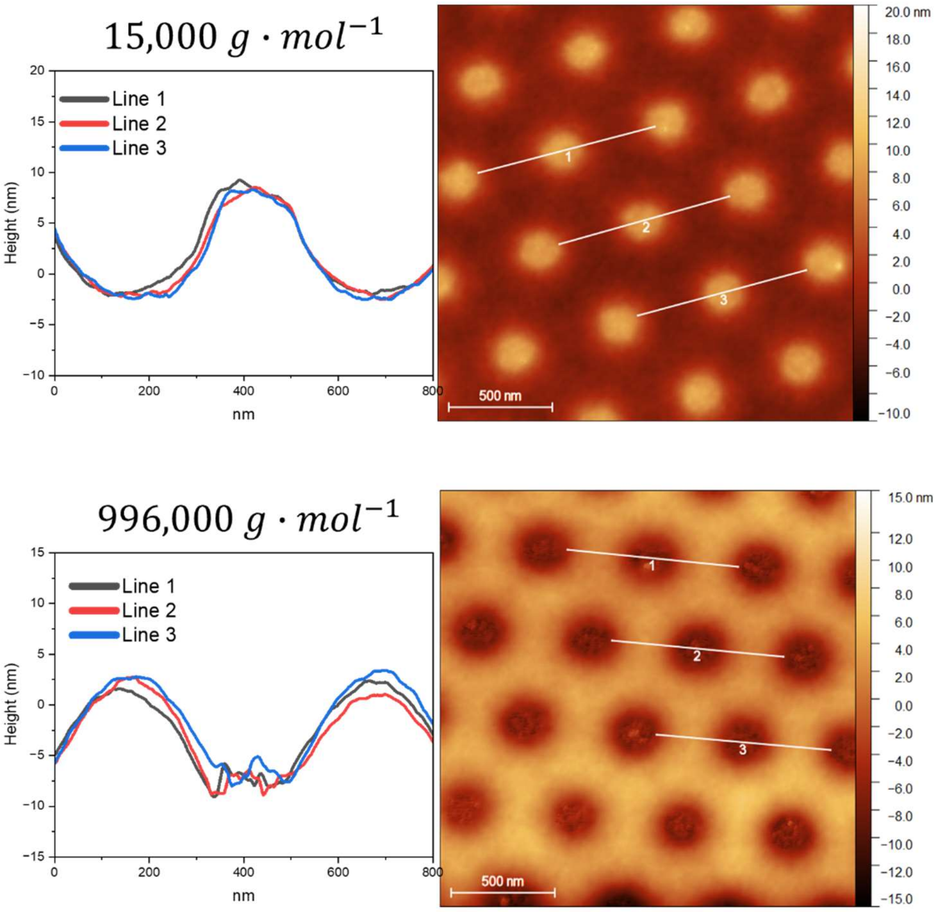

Figure 3 - AFM images and three height profiles (lines 1-3) measured on a Pt dot pattern after ASE of 15,000 g/mol and 996,000 g/mol PMMA (~40 nm) in air at 200 °C for 120 min.